## Notice of References Cited Application/Control No. O9/660,317 Examiner Monica Lewis Applicant(s)/Patent Under Reexamination CAMRAS ET AL. Page 1 of 1

## U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-4,983,009	01-1991	Musk, Robert W.	385/35
	В	US-6,214,733	04-2001	Sickmiller, Mike E.	438/691
	O	US-5,553,089	09-1996	Seki et al.	372/43
	۵	US-2002/0030194	03-2002	Camras et al.	257/98
	E	US-			
	F	US-			
	G	US-			
	Н	US-			
	ı	US-			
	J	US-			
	К	US-			
	L	US-			
	М	US-			

## **FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	0					
	Р					
	Ø					
	R					
	S					
	Т					

## **NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
	U	Sairon Technology, Bulk Measurement			
	٧	Thomas R. Anthony, Dielectric Isolation of Silicon by Anodic Bonding, 1985, pages 1240-1247.			
	w	Cerac Technical Publication, Aluminum Oxide			
	х	J.W. Osenbach et al., Low Cost/High Volume Laser Modules Using Silicon Optical Technology, IEEE Electronic Components and Technology Conference, 1998.			

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.